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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT: Gupta et al

SERIAL NO.: 10/667,202

FILED: 09/19/2003

FOR: Linear Sweeping Magnetron Sputtering Cathode and Scanning In-line System for Arc-free
Reactive Deposition and High Target Utilization

AMENDMENT

Hon. Commissioner of Patents
And Trademarks
Washington, D.C. 20231

Sir:

In response to the Office Action dated June 27, 2005 please amend the above-identified application as follows:

Amendments to the specification begin on page 2 of this paper.

Amendments to the claims begin on page 3 of this paper.

Amendments to the Drawings begin on page 10 of this paper.

Remarks begin on page 11 of this paper.